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## INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use several sheets if necessary)

Jeng H. Hwang et al.  
Applicants

December 22, 2000  
Filing Date

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Group

## U. S. PATENT DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Issue Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Filing Date If Appropriate</u>
<u>SA</u>	5,186,718	02/16/93	Tepman et al.	29	25.01	
<u>SA</u>	5,789,320	08/04/98	Andricacos et al.	438	678	
<u>SA</u>	6,030,666	02/29/00	Lam et al.	427	539	
<u>SA</u>	6,046,116	04/04/00	De Ornellas et al.	438	715	
<u>SA</u>	6,087,265	07/11/00	Hwang	438	706	

**Examiner**

**Date Considered**

Shamim Ahmed

9/4/02

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## FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Publication Date	Name	Class	Subclass	Translation If Appropriate
	DD 142966	07/23/80	Schade et al.	C23C	15/00	Abstract
	DD 285224	12/05/90	Geiler et al.	H01L	21/265	Abstract
	JP 53109475	09/25/78	Hitachi Ltd.	H01L	21/203	Abstract
	JP 1088345	04/07/98	Sukegawa Elec.	C23C	14/50	Abstract

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

SA Chow, T.P. and A. J. Steckl\*. "Plasma Etching of Refractory Gates for VLSI Applications." *J. Electrochem. Soc.* (Vol. 131, No. 10). October 1984. pp. 2325-2335.

SA Chung, C.W. and H.G. Song\*. "Study on Fence-Free Platinum Etching Using Chlorine-Based Gases in Inductively Coupled Plasma." *J. Electrochem. Soc.* (Vol. 144, No. 11). November 1997. pp. L294-L296.

SA Ye, Yan\*\*. "0.35-Micron and Sub-0.35-Micron Metal Stack Etch in a DPS Chamber-DPS Chamber and Process Characterization." *Electrochem. Soc. Proc.* (Vol. 96-12). 1996. pp. 222-233.

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